FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

LIST OF PATENTS AND PUBLICATIONS

ATTY DOCKET NO.	SERIAL NO.
23672	10/587,130

APPLICANT: Bernd RECH et al

FILING DATE	GROUP
28 December 2007	1794

U.S. PATENT DOCUMENTS

EX. INIT		DOCUMENT NO. Cntry code - No.	DATE MM-YYYY	NAME	CLASS	SUB-CLASS	FILING DATE IF APPROPRIATE
	AA	US-					
	BB	US-					
	CC	US-					

FOREIGN PATENT DOCUMENTS

		DOCUMENT NO. Cntry Code - No.	DATE MM-YYYY	COUNTRY	NAME	CLASS	TRANSL. YES	TRANSL. NO
	AI	WO 0246490	06/2003	WIPO	SZYSZKA et al			x
	AJ							
	AK							
	AJ							
	AM							
	AN							
	AO							

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

	AR	Wallendorf et al: "Optical investigation in a PEM controlled reactive magneton sputter process for aluminum doped zinc oxide layers using metallic alloy targets", Surface and Coatings Technology Vol. 147-175 (2003) pages 222-228
	AS	Szyszka et al: "Transparent and conductive ZnO:A1 film deposited by large area reactive magnetron Sputtering", Thin Solid Films vol. 442 (2003) pages 179-183
	AT	Jaeger et al: "Comparison of transparent conductive oxise thin films prepared by a.c. and d.c. reactive magnetron sputtering" Surface and Coatings Technology, vol. 98 (1998), pages 1304-1314
		Bartzsch et al: "Modeling the stability of reactive sputtering processes", Surface and Coatings Technology vol 142-144 (2001), pages 192-200
		Szyszka et al: "Optical and electrical properties of doped zinc oxide film prepares by ac reactive magnetron sputtering" Journal of Non-Crystalline Solids, vol 218, (1997) pages 74-80
		Malkomes et al: "Properties of aluminum-doped zinc oxide films deposited by high rate mid-frequency magnetron sputtering" J. Vac. Sci. Technol. A, vol. 19, no.2 (2001), pages 414-419
		Mueller et al: "State-of-the-art mid-frequency sputtered ZnO films for thin film silicon solar cells and modules" Thin solid films, vol. 442 (2003), pages 158-162
		Szyszka: "Transparent and conductive aluminum doped zinc oxide films prepared by mid-frequency reactive magnetron sputtering" Thin solid films, vol. 351 (2003), pages 164-169

EXAMINER		DATE CONSIDERED
Katz, V	/Jason Berman/	01/11/2010

EXAMINER: Initial if Reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

8 December 2009

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ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /J.B./